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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
	:	Examiner: NYA
YOSHIKAZU MIYAJIMA ET AL.)	
	:	Group Art Unit: 2811
Application No.: 10/022,506)	
	:	
Filed: December 20, 2001)	
	:	
For: EXPOSURE APPARATUS, DEVICE)	
MANUFACTURING METHOD,	:	
SEMICONDUCTOR)	
MANUFACTURING FACTORY,	:	
AND EXPOSURE APPARATUS)	
MAINTENANCE METHOD		March 26, 2002

Office of Initial Patent Examination Customer Service Center Commissioner for Patents Washington, D.C. 20231

REQUEST FOR CORRECTED FILING RECEIPT

Sir:

Applicants' attorneys have received an official Filing Receipt in the above-identified application wherein an error has been noted. The Title is incorrect and should read:

--Exposure apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method--.

A copy of the official Filing Receipt is attached with the proposed change marked in red. Issuance of a Corrected Filing Receipt with the correct data is accordingly respectfully requested.

Applicants' undersigned attorney may be reached in our New York office by telephone at (212) 218-2100. All correspondence should continue to be directed to our address given below.

Respectfully submitted,

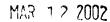
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NY_MAIN 248003 v 1





APPLICATION NUMBER

10/022.506

UNITED STATES PATENT AND TRADEMARK OFFICE

GRP ART UNIT

2811

COMMISSIONER FOR PATENTS UNITED STATES PATENT AND TRADEMARK OFFICE

WASHINGTON, D.C. 20231

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www.uspto.gov FIL FEE REC'D ATTY.DOCKET.NO DRAWINGS TOT CLAIMS IND CLAIMS

CONFIRMATION NO. 2840

Date Mailed: 01/30/2002

FILING RECEIPT

OC000000007385526

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05514 FITZPATRICK CELLA HARPER & SCINTO 30 ROCKEFELLER PLAZA NEW YORK, NY 10112

FILING DATE

12/20/2001

00862.023476

1502

862.C2476

Receipt is acknowledged of this nonprovisional Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Customer Service Center. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Yoshikazu Miyajima, Tochiqi, JAPAN; Kazuhito Outuka, Tokyo, JAPAN; Keiji Emoto, Kanagawa, JAPAN:

Domestic Priority data as claimed by applicant

Foreign Applications

JAPAN 2000-395819 12/26/2000

If Required, Foreign Filing License Granted 01/29/2002

Projected Publication Date: 06/27/2002

Non-Publication Request: No

Early Publication Request: No

Title

Exposure, apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method

Preliminary Class

257



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UNITED STATES PATENT AND TRADEMARK OFFICE





Bib Data Sheet

CONFIRMATION NO. 2840

Yoshikazu Miyajima. Tochigi. JAPAN, Kazuhito Outuka. Tokyo. JAPAN; Keiji Emoto. Kanagawa. JAPAN; "FOREIGN APPLICATIONS "JAPAN 2000-395819 12/26/2000 IF REQUIRED, FOREIGN FILING LICENSE GRANTED "01/29/2002 "Foreign Priority claimed	SERIAL NUMBER 10/022,506	FILING DATE 12/20/2001 RULE	С	257 257	GROUP ART UNIT			D	OCKET NO. 862 C2476		
FILING FEE RECEIVED 1502 FIELING FEE RECEIVED 1502 FILING FEE RECEIV	Yoshikazu Miyaj Kazuhito Outuka	a, Tokyo, JAPAN;									
Foreign Priority claimed 35 USC 119 (a-d) conditions met Altiwarder Verified and Acknowledged Examinet Altiwarder Initials ADDRESS 05514 TITLE Exposure apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method FILING FEE RECEIVED 1502 FEES: Authority has been given in Paper No to charge/credit DEPOSIT ACCOUNT	** FOREIGN APPLICA JAPAN 2000-39 IF REQUIRED, FOREI	ATIONS ************************************	<u> </u>						CO /		
TITLE Exposure apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method FILING FEE RECEIVED 1502 FEES: Authority has been given in Paper No to charge/credit DEPOSIT ACCOUNT No for following: All Fees All Fees 1.16 Fees (Filing) 1.17 Fees (Processing Ext. of time) 1.18 Fees (Issue) 1.18 Fees	Foreign Priority claimed 35 USC 119 (a-d) conditions met Verified and Acknowledged Exa	yes no Met afte		COUNTRY	DRA	WING	CLAIM		CLAIMS		
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